

文献

Montgomery, E.^a, Krahmer, C.^b, Streubel, K.^b, Hofmann, T.^a, Schubert, E.^a, Schubert, M.^a
Temperature dependent model dielectric function of highly disordered Ga_{0.52}In_{0.48}P
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抄録 (Abstract)

We report on the temperature dependence of the dielectric function of Ga_{0.52}In_{0.48}P from room temperature to 500°C, and for photon energies from 0.75 eV to 5 eV. The undoped, highly disordered Ga_{0.52}In_{0.48}P thin film was grown by metal-organic vapor phase epitaxy lattice matched onto a (001) GaAs substrate. The dielectric function of Ga_{0.52}In_{0.48}P was measured by in-situ spectroscopic ellipsometry, and analyzed using Adachi's composite critical point model. We provide a second-order temperature expansion parameter set for calculation of the Ga_{0.52}In_{0.48}P dielectric function and its temperature dependence, and which may become useful for in situ growth control or optoelectronic device performance evaluation at elevated temperatures. We discuss the temperature-induced shift of critical point transition energy parameters. © 2010 Elsevier B.V. All rights reserved.

著者キーワード

Dielectric function; Extinction coefficient; GaInP; Optical constant; Refractive index; Spectroscopic ellipsometry; Temperature dependence

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